



PATENT  
Attorney's Docket No. 3521.182

ART UNIT: 2813

EXAMINER: Tuan H. Nguyen

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:  
SOMIT TALWAR et al.

Serial No.: 10/762,861

Filed: January 22, 2004

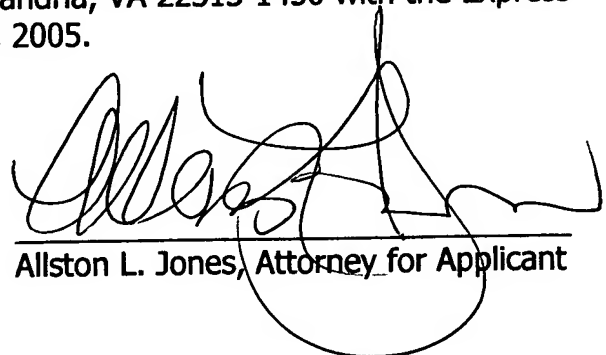
**RESPONSE TO EXAMINER'S  
RESTRICTION REQUIREMENT**

For: LASER THERMAL ANNEALING OF LIGHTLY DOPED SILICON SUBSTRATES

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

**EXPRESS MAIL CERTIFICATE**

I hereby certify that this paper, and the listed enclosures, and fee is being deposited with the United States Postal Service "Express Mail Post Office to Addressee" service under 37 CFR 1.10 on the date indicated below and is addressed to, Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450 with the Express Mail Label No. EV484314775US on October 17, 2005.



Allston L. Jones, Attorney for Applicant

Dear Sir:

The following is being submitted in response to the Examiner's Restriction Requirement within one month of the mailing dated September 29, 2005.

**Remarks**

In the Examiner's Action the Examiner stated that the claims were found to constitute two different inventions:

Group I: Claims 1-8 drawn to an apparatus; and

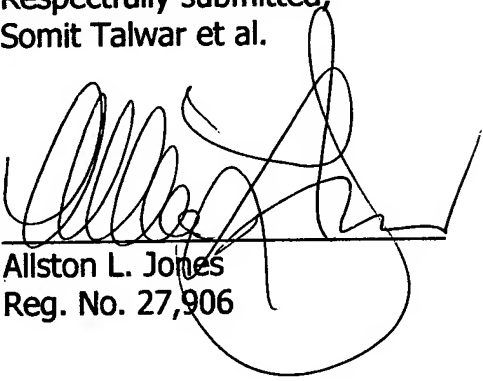
Group II: Claims 9-17 drawn to a method of preheating a substrate.

The Applicants elect to proceed with Group I claims 1-8 directed to the apparatus.

Favorable action is respectfully requested.

Respectfully submitted,  
Somit Talwar et al.

by

  
Allston L. Jones  
Reg. No. 27,906

Peters, Verny, Jones, Schmitt & Aston, LLP  
425 Sherman Ave., Suite 230  
Palo Alto, CA 94306  
Voice: 650/324-1677 (Mail Box #105)  
FAX: 650/324-1678  
e-mail: ajones888@earthlink.net  
October 17, 2005